Application No: 10/000,429 Filed: 11/30/2001 For: Dentinger.

IN THE CLAIMS

- 1. (currently amended) A photoresist composition, comprising an admixture of a phenolic resin and an onium carboxylate salt, wherein the onium carboxylate salt acts as a dissolution inhibitor the dissolution rate of said photoresist composition in aqueous base is less than about 1.3 x
- 2. (original) The photoresist composition of claim 1, wherein the onium carboxylate is an onium cholate, onium lithocholate, or onium deoxycholate.
- 3. (original) The photoresist composition of claim 2, wherein the onium cholate is an iodonium cholate.
- 4. (original) The photoresist composition of claim 3, wherein the iodonium cholate is an alkyloxyphenylphenyl iodonium cholate.
- 5. (original) The photoresist composition of claim 4, wherein the alkyloxyphenylphenyl iodonium cholate is octyloxyphenyphenyl iodonium cholate.
- 6. (original) The photoresist composition of claim 1, wherein the phenolic resin is novolac.
- 7. (original) The photoresist composition of claim 1, wherein the onium carboxylate is present in an amount of at least 20 wt%.
- 8. (original) The photoresist composition of claim 1, wherein said photoresist composition can withstand pre-exposure baking temperatures of at least 125 °C.
- 9. (cancelled) The photoresist composition of claim 1, wherein the dissolution rate of said photoresist composition in aqueous base is less

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than about $1.3 \times 10^{-4} \mu m/sec$.

10. (original) A single component photoresist composition, comprising an onium cation protected carboxylate polymer.

- 11. (original) The photoresist composition of claim 10, wherein the polymer is an acrylic/acrylic acid copolymer.
- 12. (original) The photoresist composition of claim 11, wherein the copolymer is a methacrylic/acrylic acid copolymer.
- 13. (original) The photoresist composition of claim 10, wherein the onium cation is an iodonium cation.
- 14. (original) The photoresist composition of claim 13, wherein the iodonium cation is an alkyloxyphenylphenyl iodonium cation.
- 15. (original) The photoresist composition of claim 14, wherein the alkyloxyphenylphenyl cation is an octyloxyphenylphenyl iodonium cation.
- 16. (original) The photoresist composition of claim 10, wherein the onium cation is present at a concentration of at least 25 mole%.